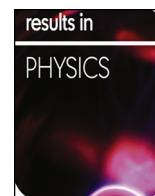




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## Nano-capacitor-like model using light trapping in plasmonic island embedded microring system

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## A B S T R A C T

We have proposed the convincing electro-optic circuit for long life-time electron mobility emission. Light a monochromatic source is utilized as input into the circuit via the input port and trapped within the plasmonic island. It is a formed-like capacitor structure formed by the silicon-graphene-gold materials which are stacked layers. All circuit port ends have added the TiO<sub>2</sub> to form the reflectors. By selecting the suitable parameters, the fraction of the output power emission can be controlled at the add port, from which it can be successively pumping and trapped(stored) within the plasmonic island. The system energy saturation can be released by squeezing light behavior, therefore, the system is always balanced due to the successive pumping process. The results obtained of the single cell(circuit) have shown that the charging time and discharging times of the nano-capacitor-like of ~2 to 3 s and 1000 h are achieved. This can be applied to long life mobility emission (discharge) of the capacity-like device. The mobility storage time within the island is 14,000 h, with the electron mobility of  $\sim 3.0 \times 10^{-7} \text{ cm}^2 \text{ Vs}^{-1}$  is obtained.

## Introduction

Light trapping within a micro-scale device has become the promising technique for various applications, where there are many types of research and investigations in various investigations [1–5]. Energy storage using the light trapping technique is also the interesting method for long life power emission. Many works in both theory and practice have been reported [6–11], where there were different trapping systems applied. The key advantage of them is the tiny trapping system with the suitable materials could offer different applications. Light trapping within a microring system is also the interesting technique for energy storage [12], in which the electro-optic energy conversion can be formed and used for battery [13]. The electro-optic conversion can be formed by using the device called the plasmonic island and stacked layers, in which light energy can be converted to be the electron mobility and current, which can be used as the charge and discharge current for battery applications. Principally, the light intensity can be

converted to be the electron mobility by using the following relationship as  $I = E^2 = \left(\frac{V_d}{\mu}\right)^2$ . Here, the light intensity is presented by  $I$ , and the group velocity is defined as  $V_d = \mu E$ . An electric current can be established in the conductor once an electric field of  $E$  is applied in the grating sensor, where the current density can be defined as  $J_s = \sigma E$ . Here, the conductance or the electrical conductivity is defined by  $\sigma$ , where for the gold material it is  $1.6 \times 10^8 \text{ W}^{-1} \text{ m}^{-1}$  [14,15]. By modifying the microring resonator design as add-drop filter consisting of two microring resonators attached to the centred ring, we can induce the nonlinear effects to the system which offers a generation of short pulses and easy control of the WGM resonance output compared with the original microring resonator design [16–18]. The sensitivity of the system can be obtained by the relationship between the electron mobility output and the applied current (input power). By using the plasmonic island, the plasmonic waves are introduced in the graphene layer by the input light intensity from the silicon layer, from which the

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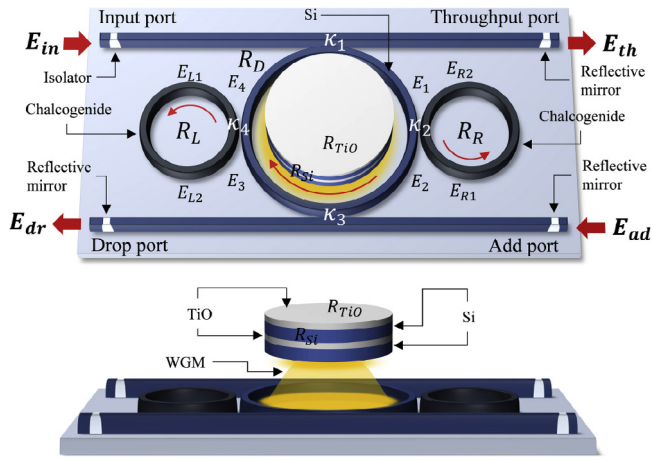
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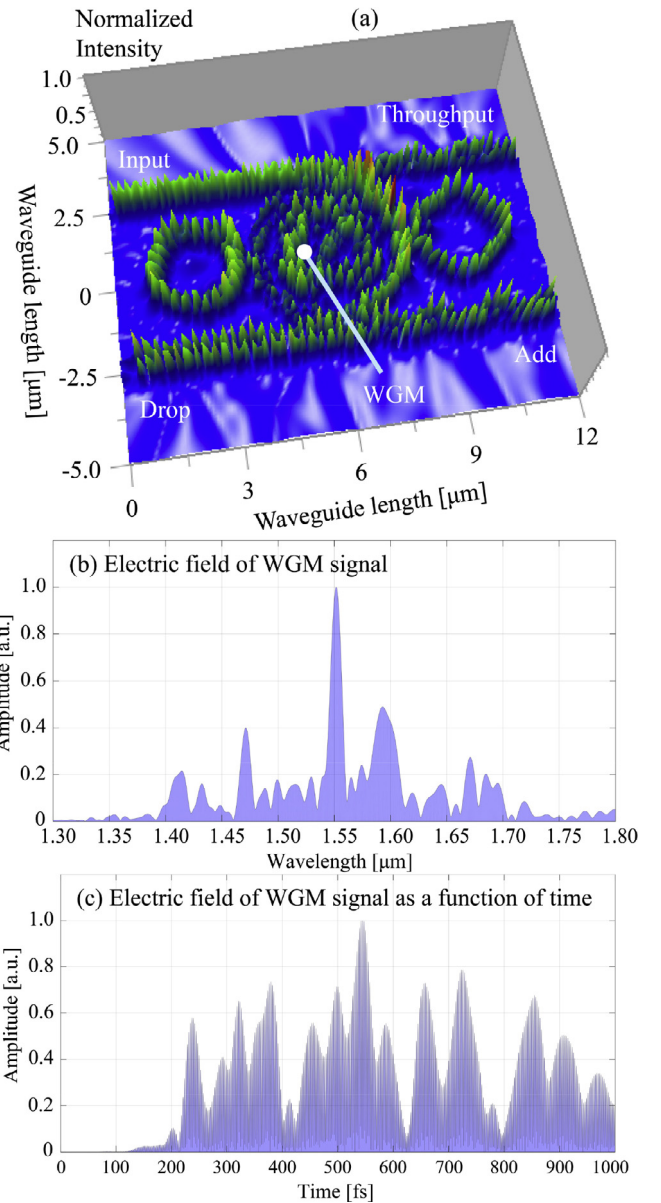
**Fig. 1.** Schematic of a plasmonic island structure, where  $E_{in}$ ,  $E_{th}$ ,  $E_{dr}$ ,  $E_{ad}$  are the electrical fields of the input, through, drop and add ports,  $R_L$ ,  $R_R$ ,  $R_D$  are the ring radii of the left, right, and center ring, respectively,  $\kappa_s$ : the coupling coefficients are 0.5. Si: Silicon,  $R_{Si}$ : Silicon ring radius,  $R_{TiO}$ : Titanium oxide circle radius.

electron mobility is driven by the surface plasmon waves. The excited electrons are conducted within the gold layer by the driven plasmonic waves. In this article, the trapping light within the Panda-ring circuit is controlled to have the low-emission rate by the applied reflector length (coefficient). The silicon device on-chip with the scale less than  $1 \mu\text{m}$  has been recently reported, however, this work the device is formed by the ChG microring structure, in which the device scale is proposed by the practical fabrication scale [19]. The low energy (electron mobility) emission is configured by the black-body-radiation. The system is fed by the external energy, then it is almost closed during the operation.

The generated electro-optic signal conversion within the system in Fig. 1 can be obtained by the relationship between the plasmon wave energy and electron mobility within the gold layer [20]. The driven group velocity within the device can generate the required WGM beam output. By adjusting the input power and also the phase modulator which is realized as two nonlinear ring sides, the whispering gallery mode can be controlled. Suitable pumping power can be applied to the center wavelength signal and the resonant pulse width by using the nonlinear materials such as ZnO. Here, the resonance pulse width is defined as switching time. Eq. (1) representing the electrical output field ( $E_{WGM}$ ) in the cylindrical coordinator [17]. To simplify the equation, the surface reflection of the reflector is neglected, where  $I_{WGMR} = -R_{WGM} I_{WGM}$ .  $R_{WGM}$  which is the reflection output. Here,  $R_{WGM}$ , is the reflection coefficient or the reflectivity of the used material [21]. Further investigations can be performed by using different filters, as the output from the circuit can interfere with the reflection power, where the results from the interference output can be detected and seen in the output ports of the system. To obtain such interference results we have selected simulation system parameters from experimental works [22,23]. The used parameters are given in the captions of relevant figures. In Fig. 1, a selected light source is fed into the system via an input port, which is represented as the input electric field ( $E_{in}$ ). The electric fields are circulated within the system and described by the Eqs. (1)–(3) [21], the input electric field is fed into the z-axis, where  $E_{in} = E_z = E_0 e^{-ik_z z - i\omega t + \varphi}$ ,  $E_0$  is the initial electric field amplitude, Where  $E_0$  is the electric field amplitude (real),  $k_z$  is the wave number in the direction of propagation (z-axis) and  $\omega$  is the angular frequency, where  $\varphi$  is the phase of light.

$$E_{th} = \sqrt{1-\gamma_1} \left( \sqrt{1-\kappa_1} E_{in} + j\sqrt{\kappa_1} E_4 e^{-\frac{\alpha}{2} \frac{L_D}{4} - jk_n \frac{L_D}{4}} \right) \quad 1$$

$$E_{dr} = \sqrt{1-\gamma_3} \left( \sqrt{1-\kappa_3} E_{add} + j\sqrt{\kappa_3} E_2 e^{-\frac{\alpha}{2} \frac{L_D}{4} - jk_n \frac{L_D}{4}} \right) \quad 2$$



**Fig. 2.** Wave propagation results within the system shown in Fig. 1, where the input power is 2 W, and the center wavelength is  $1.55 \mu\text{m}$ . The ring system,  $R_L = R_R = 1.1 \mu\text{m}$ ,  $R_D = 2.0 \mu\text{m}$ ,  $\kappa_1 = \kappa_2 = \kappa_3 = \kappa_4 = 0.5$ ,  $n_{ochg} = 2.9$ ,  $n_{2chg} = 1.02 \times 10^{-17} \text{m}^2 \text{W}^{-1}$  [25],  $n_{Si} = 3.47$  (Si-Crystalline silicon), where (a) the graphical results, (b) the electric field signal as a function of wavelength, and (c) the electric field signal as a function of time.

$$E_{out} = \sqrt{1-\gamma_5} \left( \sqrt{1-\kappa_3} E_{dr}^* + j\sqrt{\kappa_3} E_2 e^{-\frac{\alpha}{2} \frac{L_D}{4} - jk_n \frac{L_D}{4}} \right) \quad 3$$

Here,  $E_{dr}^* = -nE_{dr}$ .  $n$  is the reflection ratio,  $E_{out}$  is the electric field output from the add port,  $E_1$ ,  $E_2$ ,  $E_3$ , and  $E_4$  are the electric fields in the system.  $\gamma_s$  are the intensity insertion loss coefficients of the 3 dB couplers, and  $\kappa_{is}$  are the coupling constants.  $\alpha$  is the attenuation loss of light in the waveguide, and  $k_n = \frac{2\pi}{\lambda} n_{eff}$  is the propagation constant,  $L_D$  is the circumference of the center ring.

The suitable system parameters were achieved by using the graphical approach called the Optiwave program, from which the MATLAB program is used for numerical calculation. The parameters of the device are indicated in the figure captions. Fig. 1 shows the system, wherein the wave propagates within the system is shown in Fig. 2, where the Optiwave is used to perform the simulations. Here, the input power of 2 W at  $1.55 \mu\text{m}$  is used. The ring radii are  $R_L = R_R = 1.1 \mu\text{m}$ ,

$R_D = 2.0 \mu\text{m}$ . The coupling constants are  $\kappa_1$  to  $\kappa_4 = 0.5$ , the refractive indices are  $n_{\text{OchG}} = 2.9$ ,  $n_{2\text{ChG}} = 1.02 \times 10^{-17} \text{ m}^2 \text{ W}^{-1}$  [24,25],  $n_{\text{Si}} = 3.47$  (Si-Crystalline silicon), where (a) the graphical results, (b) the electric field signal as a function of wavelength, and (c) the electric field signal as a function of time. The other parameters are given by the following details. We define the carrier density as  $n = [(\text{Density}) \times (\text{free electron number per atom}) \times (\text{Avogadro's constant}) \times 10^6] / [\text{Molar mass}]$  electrons per cubic metre. For  $\text{TiO}_2$ , the density is  $4.95 \text{ g cm}^{-3}$ , the Avogadro's constant is  $6.02 \times 10^{23}$  atoms, the free electron number is 1, the Molar mass is  $63.866 \text{ g mol}^{-1}$ , and the conductivity,  $\sigma = 2.38 \times 10^6 \text{ Sm}^{-1}$  [26]. Then the charge-carrier number density for the  $\text{TiO}_2$  can be calculated as  $n = [4.95 \times 1 \times (6.02 \times 10^{23}) \times 10^6] / 63.866 = 4.6659 \times 10^{28}$  electrons- $\text{m}^{-3}$ . The  $\text{TiO}_2$  island radius ( $R_{\text{TiO}}$ ) and thickness are  $1.6 \mu\text{m}$  and  $0.1 \mu\text{m}$ , respectively. The charge-carrier number can be calculated as  $(4.6659 \times 10^{28}) \times \pi \times (1.6 \times 10^{-6})^2 \times (0.1 \times 10^{-6}) = 3.7525 \times 10^{10}$  electrons, where an electron itself has a negative charge of approximately  $1.602 \times 10^{-19} \text{ C}$  [26]. Thus, the maximum electrical charge of the island is  $Q_{\text{max}} = [3.7525 \times 10^{10}] \times [1.602 \times 10^{-19}] = 6.0115 \times 10^{-9} \text{ C}$ . The charge in time on a system of two parallel conductive plates, which is a capacitor, can be calculated as the electric charge divided by the charging current. In addition, the current density,  $J$ , is the product between the electric field,  $E$ , inside the material and of which the conductivity,  $\sigma$ , that related to the material length (the thickness of the plate;  $T_{\text{TiO}}$ ). Therefore, the charging current,  $I$ , can be calculated by  $I = JA = \sigma T_{\text{TiO}} EA$ , where  $A = \pi [R_{\text{TiO}}]^2$  is the cross-section area of the material (area of the plates). In addition, the charge  $Q$  on a capacitor relates to the charging current  $I$  (coulombs $^{-1}$ ), which can be expressed as  $Q = t \times I$ , where  $t$  is the charging time. Therefore, the time-dependent charge of the capacitor in the plasmonic island can be considered as  $Q(t) = [t \times \sigma T_{\text{TiO}} EA]$ . The relationship of the charging  $Q$  as a function of time can be illustrated as in Fig. 3(a), in which the discharging time will depend on the applied loads. For simplicity, we suppose the plasmonic island charge is

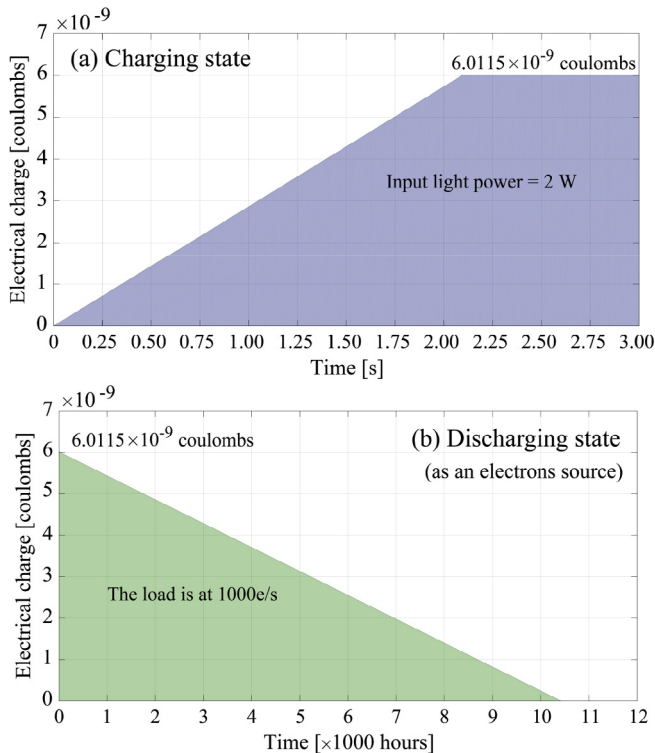


Fig. 3. Simulation result of the nano-capacitor-like characteristics using the system in Fig. 1, where (a) the charging state, where the input light power is at 2 W, and (b) the discharging state, where the applied load current is 1000 e/s.

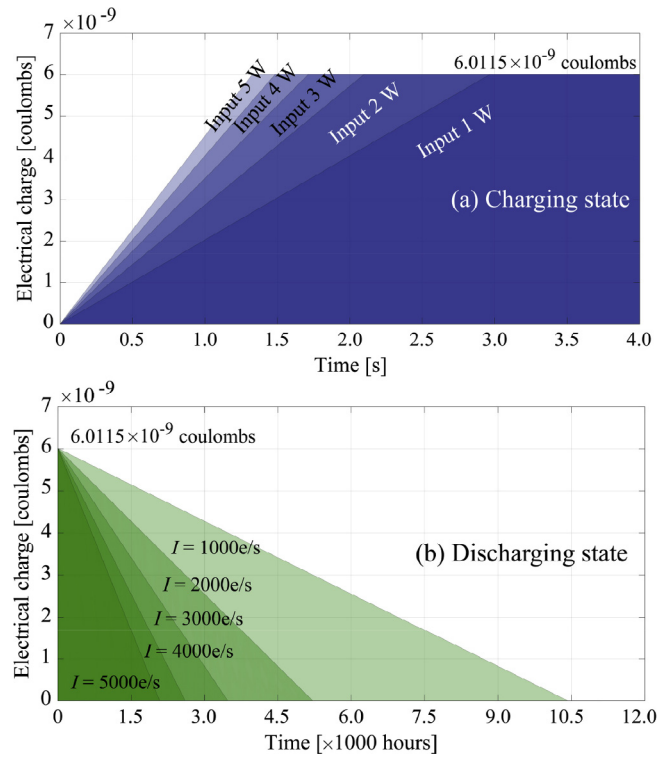


Fig. 4. Plots of the input power and charging and discharging time, where  $R_{\text{TiO}} = 1.6 \mu\text{m}$  and the thickness of each  $\text{TiO}_2$  is  $0.1 \mu\text{m}$ , and the titanium plate separation ( $d$ ) is  $0.2 \mu\text{m}$ . The applied load is varied from 1000 e/s to 5000 e/s, where (a) the charging state, (b) the discharging state. The charging time is less than 3 s in all cases, while the discharging time of 10,000 hours is obtained.

at the maximum ( $Q_{\text{max}}$ ). The load driving current is the amount of  $Q$  per time, which is the electron source. Thus, the discharging  $Q$  as a function of time can be considered by  $Q(t) = [Q_{\text{max}} - met]$ , where  $m$  is an amount of discharging electron per time,  $e$  is the electron charge number approximately of  $1.602 \times 10^{-19} \text{ C}$ , and  $t$  is time.

Similarly, the discharging state can be illustrated as in Fig. 3(b). Plots of the input power and charging and discharging time is shown in Fig. 4, where  $R_{\text{TiO}} = 1.6 \mu\text{m}$ , the reflector thickness ( $\text{TiO}_2$ ) is  $0.1 \mu\text{m}$ , and the  $\text{TiO}_2$  plate separation ( $d$ ) is  $0.2 \mu\text{m}$ . The applied load is varied from 1000 e/s to 5000 e/s, where (a) the charging state, (b) the discharging state. The plot of the (stored) electron mobility in the island is shown in

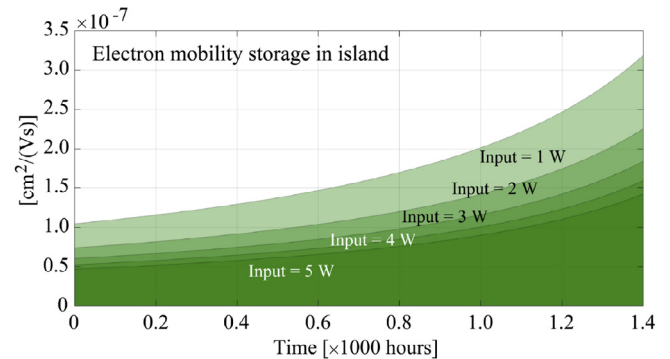


Fig. 5. Plot of the (stored) electron mobility in the island, where the load is drawn current is 1000 e/s from the island capacitor. The Titanium oxide layer parameters are  $R_{\text{TiO}} = 1.6 \mu\text{m}$ , thickness  $T_{\text{TiO}} = 0.1 \mu\text{m}$ . The electron mobility is  $\mu = V_d/E$ , where  $V_d$  is the drift velocity, which is  $V_d = j_s/ne$ , where  $j_s = \sigma T_{\text{TiO}} E$  is the current density flowing through the material,  $e$  is the electron charge number, and  $n$  is the charge-carrier number density. The storage electron mobility can be reached the value of of  $1.0 \times 10^{-7} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$  within 15 min.

Fig. 5. For simplicity, we suppose that the load drawn current is 1000 e/s from the island capacitor, which corresponds to the amount of Q per time. The titanium oxide layer parameters are  $R_{TiO} = 1.6 \mu\text{m}$ , thickness  $T_{TiO} = 0.1 \mu\text{m}$ . In the calculation, the electron mobility,  $\mu = V_d/E$ , where  $V_d$  is the drift velocity, which is  $V_d = j_s/ne$ , where  $j_s = \sigma T_{TiO} E$  is the current density flowing through the material,  $e$  is the electron charge number, and  $n$  is the charge-carrier number density (electrons per cubic metre). The stored electron mobility tends to increase when the electrons are drawn by the applied loads.

We have proposed the use of the capacitor-like circuit using the plasmonic island embedded microring system, which consists of a semi-closed microring resonator system. The input light energy is entered into the system and the successive pumping occurred. The charge process of the electron mobility is generated within the plasmonic island, which is formed by the capacitor-like circuit. By using the electro-optic energy conversion, the charge and discharge characteristics of the device are simulated and interpreted. The full electrical charge and discharge capacity can be achieved within 2–3 s and 1000 h, respectively, while the mobility discharge (emission) is controlled by the coated reflected end at the add port. The stored electron mobility within the island (nano-capacitor-like device) of  $3.0 \times 10^{-7} \text{ cm}^2 \text{Vs}^{-1}$  at 14,000 h is obtained. In application, the reflector at the drop port can be arranged to achieve the required discharge time and current. Additionally, the large volume of the circuits can be constructed and the more charge capacity values can be obtained, where the capacitors can be connected to form the circuits to obtain the higher capacitance. The device scale and materials can be found in the currently available materials, where the device scale can be supported by the current fabrication technology. The proposed system is almost a closed that can be used for the black-body radiation of the store energy, which may be useful for other investigations.

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## Appendix A. Supplementary material

Supplementary data associated with this article can be found, in the online version, at <https://doi.org/10.1016/j.rinp.2018.07.013>.

## References

- [1] Mitatha S, Kamoldilok S, Yupapin PP. White light generation and amplification using a soliton pulse within a nano-waveguide for potential of solar energy conversion use. *Energy Convers Manage* 2010;51:2340–4.
- [2] Kamoldilok S, Yupapin PP. Nanoheat source generated by leaky light mode within a nano-waveguide for small electrical generator. *Energy Convers Manage* 2012;64:23–7.
- [3] Srithanachai I, Uemmanapong S, Niemcharoen S, Yupapin PP. Novel design of solar cell efficiency improvement using an embedded electron accelerator on-chip. *Opt Express* 2012;20:12640–8.
- [4] Ali J, Pornsuwancharoen N, Youplao P, et al. Coherent light squeezing states within a modified microring system. *Results Phys* 2018;9:211–4.
- [5] Pornsuwancharoen N, Amiri IS, Suhailin FH, Aziz MS, Ali J, Singh G, Yupapin P. Micro-current source generated by a WGM of light within a stacked silicon-graphene-Au waveguide. *IEEE Photon Technol Lett* 2017;29:1768–71.
- [6] Sasithitlu K, Dahan N, Greffet JJ. Light trapping in ultrathin CIGS solar cell with absorber thickness of 0.1  $\mu\text{m}$ . *IEEE J Photovoltaics* 2018;8:621–5.
- [7] Gupta ND, Janyani V. Lambertian and photonic light trapping analysis with thickness for GaAs solar cells based on 2D periodic pattern. *IET Optoelectron* 2017;11:217–24.
- [8] Goffard J, Colin C, Mollica F, Cattoni A, Sauvan C, et al. Light trapping in ultrathin CIGS solar cells with nanostructured back mirrors. *IEEE J Photovoltaics* 2017;7:1433–41.
- [9] Gupta ND, Janyani V. Design and analysis of light trapping in thin film GaAs solar cells using 2-D photonic crystal structures at front surface. *IEEE J Quantum Electron* 2017;53:4800109.
- [10] Nirmal A, Kyaw AKK, Jianxiong W, Dev K, Sun X, et al. Light trapping in inverted organic photovoltaics with nanoimprinted ZnO photonic crystal. *IEEE J Photovoltaics* 2017;7:545–9.
- [11] Pornsuwancharoen N, Amiri IS, Suhailin FH, et al. Micro-current source generated by a WGM of light within a stacked silicon-graphene-Au waveguide. *IEEE Photon Technol Lett* 2017;29:1768–71.
- [12] Ali J, Youplao P, Pornsuwancharoen N, et al. On-chip remote charger model using plasmonic island circuit. *Results Phys* 2018;9:815–8.
- [13] Zainol FD, Jomtarak R, Daud D, Teeka C, Ali J, Yupapin PP. Atom bottom-up manipulation controlled by light for microbattery use. *IEEE Trans Nanotechnol* 2012;11:934–9.
- [14] Gall D. Electron mean free path in elemental metals. *J Appl Phys* 2016;119:085101.
- [15] Baccarani G, Ostojia P. Electron mobility empirically related to the phosphorus concentration in silicon. *Solid-State Electron* 1975;18:579–80.
- [16] Sarapat N, Frank TD, Yupapin PP. Conjugate mirror design and simulation using a nonlinear coupling microring circuit. *J. Nonlinear Opt Phys Mater* 2013;22:1350024.
- [17] Phatharacorn P, Chiangga S, Yupapin P. Analytical and simulation results of a triple micro whispering gallery mode probe system for a 3D blood flow rate sensor. *Appl Opt* 2016;55(33):009504.
- [18] Pornsuwancharoen N, Youplao P, Amiri IS, Ali J, Yupapin P. Electron driven mobility model by light on the stacked metal-dielectric interfaces. *Microwave Opt Technol Lett* 2017;59:1704–9.
- [19] Suwanarat S, Chiangga S, Amiri IS, et al. On-chip supercontinuum generation in nanostructured  $\text{Ge}_{11.5}\text{As}_{24}\text{Se}_{64.5}$  chalcogenide waveguides using panda-ring. *Results Phys* 2018;10:38–44.
- [20] Soysouvanh S, Jalil M, Amiri IS, et al. Ultra-fast electro-optic switching control using a soliton pulse within a modified add-drop multiplexer. *Microsyst Technol* 2018;1–6. Early Online.
- [21] Chaiwong K, Tamee T, Punthawanunt S, et al. Naked-eye 3D imaging model using the embedded micro-conjugate mirrors within the medical micro-needle device. *Microsyst Technol* 2018;24:2695–9.
- [22] Atabaki AH, Moazenni S, Pavanello F, et al. Integrating photonics with silicon nano-electronics for next generation of system on a chip. *Nature* 2018;556:349–54.
- [23] Koos C, Jacome L, Poulton C, et al. Nonlinear silicon-on-insulator waveguides for all-optical signal processing. *Opt Express* 2007;15:5976–90.
- [24] Smektala F, Quemard C, Leneindre L, Lucas J, Barthélémy A, De Angelis C. Chalcogenide glasses with large non-linear refractive indices. *J Non-Cryst Solids* 1998;239:139–42.
- [25] Mohr PJ, Newell DB, Taylor BN. CODATA recommended values of the fundamental physical constants. 2014. *Rev Mod Phys* 2016;88. 035009-1-73.
- [26] Banus MD, Reed TB, Strauss AJ. Electrical and magnetic properties of TiO and VO. *Phys Rev B* 1972;5:2775.